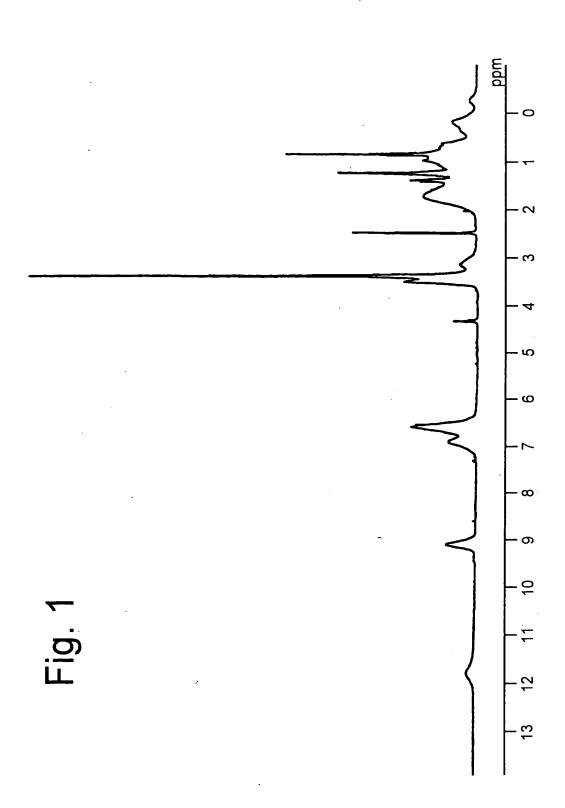
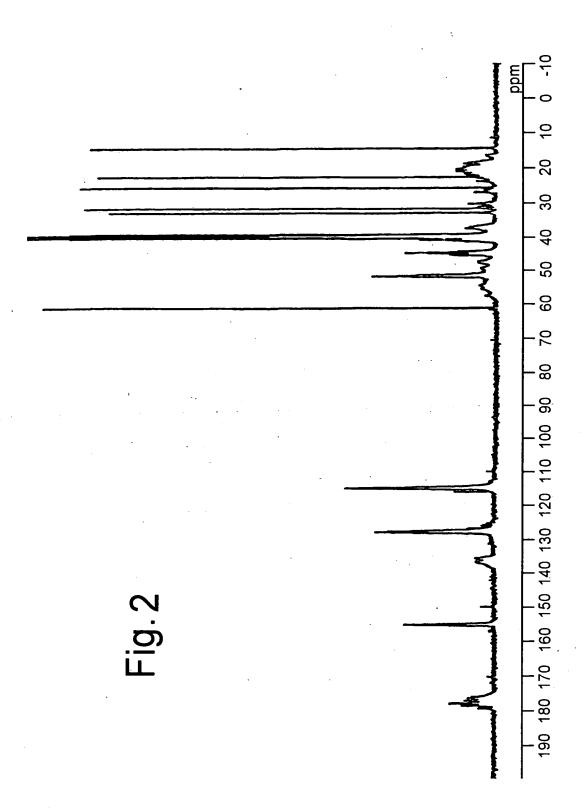
APPLN. FILING DATE: JULY 28, 2003
TITLE: POSITIVE SENSITIVE RESIN COMPOSITION AND A PROCESS FOR FORMING A RESIST PATTERN THEREWITH

Inventor(s): Genji IMAI et al. Docket No: 029430-553

SHEET 1 of 5



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TITLE: POSITIVE SENSITIVE RESIN COMPOSITION AND A
PROCESS FOR FORMING A RESIST PATTERN THEREWITH
INVENTOR(S): GENII IMAI ET AL.
DOCKET NO: 029430-553
SHEET 2 of 5



APPLN. FILING DATE: JULY 28, 2003

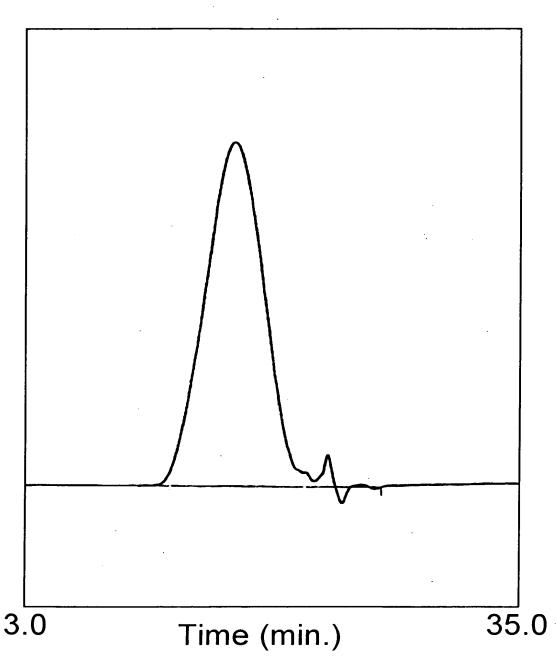
TITLE: POSITIVE SENSITIVE RESIN COMPOSITION AND A PROCESS FOR FORMING A RESIST PATTERN THEREWITH

INVENTOR(S): GENJI IMAI ET AL.

DOCKET NO: 029430-553

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Fig. 3



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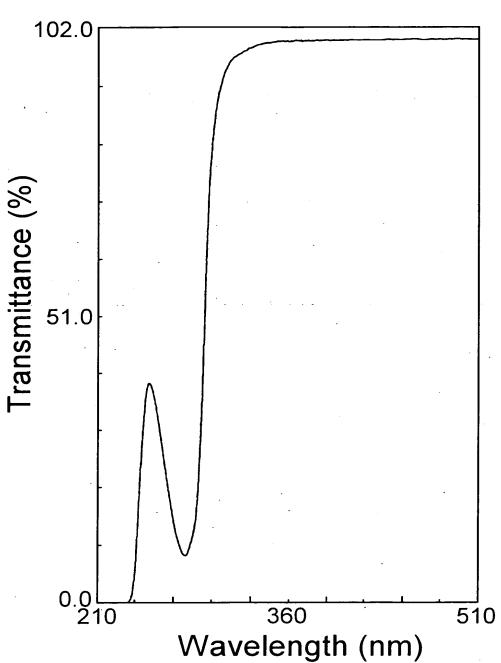
TITLE: POSITIVE SENSITIVE RESIN COMPOSITION AND A PROCESS FOR FORMING A RESIST PATTERN THEREWITH

INVENTOR(S): GENJI IMAI ET AL.

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Fig. 4



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